

3 2
~~19.~~ The polishing pad of claim ~~18~~, wherein the transparent section extends through the first layer.

4 2
~~20.~~ The polishing pad of claim ~~18~~, wherein the aperture extends through the second layer.

5 1
~~21.~~ The polishing pad of claim ~~17~~, wherein the transparent section and the aperture have substantially the same dimension.

6 1
~~22.~~ The polishing pad of claim ~~17~~, wherein a top surface of the transparent section is substantially coplanar with the polishing surface.

23. A polishing pad for a chemical mechanical polishing apparatus, comprising:
a first layer having a polishing surface and a transparent section; and
a second layer adjacent to the first layer having an aperture substantially aligned with the transparent section.

8
~~24.~~ The polishing pad of claim ~~23~~, wherein the first layer is formed of a polyurethane material.

25. The polishing pad of claim 25, wherein the transparent section is formed of a polyurethane material.

10 7
~~26.~~ The polishing pad of claim ~~23~~, wherein the second layer is a backing layer.

27. A polishing pad for a chemical mechanical polishing apparatus, comprising:

A

an article having a polishing surface and a substantially transparent section, the transparent section having a first portion with a first dimension and a second portion with a second, different dimension.

12 11
28. The polishing pad of claim 27, wherein the article includes a first layer with the polishing surface and a second layer adjacent to the first layer.

13 12
29. The polishing pad of claim 28, wherein the transparent section extends through the first and second layers.

14 13
30. The polishing pad of claim 29, wherein the first section of the aperture extends through the first layer and the second section of the aperture extends through the second layer.

15
31. A chemical mechanical polishing apparatus, comprising:
a carrier head to hold a substrate;
a polishing pad having a polishing surface and a surface opposite the polishing surface, the polishing pad including a first layer having a polishing surface with a transparent section and a second layer adjacent to the first layer having an aperture substantially aligned with the transparent section; and
a motor to generate relative motion between the carrier head and the polishing pad.

16 15
32. The apparatus of claim 31, further comprising a platen to support the polishing pad.

17 16
AL 33. The apparatus of claim 32, wherein the second layer abuts the platen.

18 17
AL 34. The apparatus of claim 33, wherein a passage is formed in the platen, and the passage is substantially aligned with the aperture in the polishing pad.

A